

Title (en)  
COMPOSITIONS AND METHODS FOR INHIBITING INFLAMMATION OF VESSEL WALLS AND FORMATION OF NEOINTIMAL HYPERPLASIA

Title (de)  
ZUSAMMENSETZUNGEN UND METHODEN UM DIE ENTZÜNDUNG VON GEFÄSSWÄNDEN UND DIE BILDUNG VON NEOINTIMALER HYPERPLASIE ZU HEMMEN

Title (fr)  
COMPOSITIONS ET PROCEDES PERMETTANT D'INHIBER L'INFLAMMATION DES PAROIS VASCULAIRES ET LA FORMATION D'HYPERTROPHIE DE NEO-INTIMA

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**EP 1601696 A1 20051207 (EN)**

Application  
**EP 04717875 A 20040305**

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Abstract (en)  
[origin: WO2004078786A1] Compositions and methods for inhibiting inflammation of vessel wall and/or formation of neointimal hyperplasia by gene therapy using a soluble Flt-1 (sFlt-1) gene, are provided. VEGF has an essential role in the development of neointimal hyperplasia by causing inflammation. sFlt-1 gene transfer to the site of vascular injury blocks Flt-1-mediated VEGF signal transduction, thereby inhibiting early inflammation as well as late neointimal hyperplasia. The present invention is useful for inhibiting or treating inflammation of vessel wall and/or formation of neointimal hyperplasia in a patient with risk of post coronary intervention restenosis, atherosclerosis, arteriosclerosis, or edema.

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Citation (search report)  
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Citation (examination)  
SHIBATA M. ET AL., HISTOCHEM CELL BIOL., vol. 116, 2001, pages 471 - 481

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